




Mandatory chemical and physical requirements									
	American ASTM C1240 – 04	European EN 13263:2005	Canadian CAN/CSA A23.5 - 98	Japanese JIS A 6207 2000	Chinese GB/T18736 -2002	Brazilian NBR 13956:1997	Korean KS F 2567 2003	Vietnamese TCXDVN 311 - 2003	Indian IS 15388:2003
SiO ₂ (%)	> 85,0	> 85	> 85	> 85	> 85	> 85	> 85	> 85	> 85,0
SO ₃ (%)		< 2,0	< 1,0	< 3,0			< 3,0		
Cl (%)		< 0,3		< 0,1	< 0,2		< 0,3		
Free CaO (%)		< 1,0		< 1,0					
MgO (%)				< 5,0			< 5,0		
Free Si (%)		< 0,4							
Available alkalis (Na ₂ O equivalent, %)	Report					< 1,5			< 1,5
Moisture (%)	< 3,0			< 3,0	< 3,0	< 3,0		< 3,0	< 3,0
Loss on Ignition (%)	< 6,0	< 4,0	< 6,0	< 5,0	< 6,0	< 6,0	< 5,0	< 6,0	< 4,0
Specific surface (m ² /gram)	> 15	15 - 35		> 15	> 15		> 15		> 15
Bulk density, undensified	Report								
Pozzolanic Activity Index (%)	> 105 @ 7d, accel. curing	> 100 @ 28d, std curing		> 95 @ 7d > 105 @ 28d, std curing	> 85 @ 28d, std curing		> 95 @ 7d, accel. curing	> 85 @ 7d	> 85,0 @ 7d, 27 °C curing
Retained on 45 micron sieve (%)	< 10		< 10			< 10	< 5,0	< 10	< 10
Variation from average on 45 micron sieve (%-points)	< 5								< 5
Density (kg/m ³)	Report								
Autoclave expansion (%)			< 0,2						
Foaming			No foam						
Dry mass (%-points deviation from declared in slurry)		< 2					< 2		
Water requirement ratio (%)					< 125				

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